



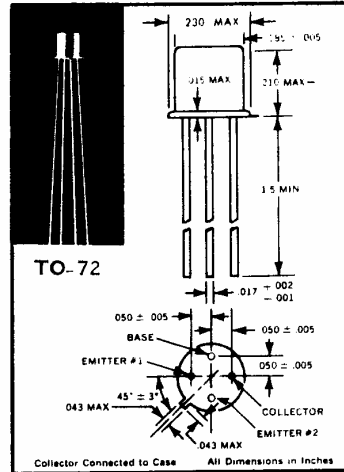
**HIGH VOLTAGE
SILICON EPITAXIAL JUNCTION
INTEGRATED CHOPPER TRANSISTOR**

**3N108
3N109
3N110
3N111**

- LOW LEAKAGE
- LOW C_{eb}
- LOW $r_{EE} (sat)$
- HIGH V_{EE} & V_{EB}

ELECTRICAL DATA ABSOLUTE MAXIMUM RATING

PARAMETER	SYMBOL	3N108/109	3N110/111	UNITS
Collector-Base Breakdown Voltage	BV_{bc}	-50	-50	V
Emitter-Base Breakdown Voltage	BV_{E1B}	-50	-30	V
Emitter-Base Breakdown Voltage	BV_{E2B}	-50	-30	V
Emitter To Emitter Breakdown Voltage	BV_{E1E2}	± 50	± 30	V
Emitter (1) To Collector Breakdown Voltage	BV_{E1C}	-50	-30	V
Emitter (2) To Collector Breakdown Voltage	BV_{E2C}	-50	-30	V
DC Collector Current	I_c	20	20	mA
DC Base Current	I_b	20	20	mA
DC Emitter Current	I_e	10	10	mA
Power Dissipation (Free Air)	P_c	300mW Derating 1.7mW/°C		
Junction Temp. (Oper. & Store)	T_j	-65°C to +200°C		
Lead Temp. (1/16" \pm 1/32" From Case)	T_L	300°C for 10 Sec.		



ELECTRICAL CHARACTERISTICS: $T_j = 25^\circ C$ (UNLESS OTHERWISE STATED)

PARAMETER	SYMBOL	CONDITION	3N108/110		3N109/111		UNITS
			MIN.	MAX.	MIN.	MAX.	
Offset Voltage	V_{E1E2}	$I_B = 1mA, Temp: -25/+25/+100^\circ C$		30		150	μV
Offset Voltage Change	ΔV_{E1E2}	$I_B = 1mA, Temp: -25 to +100^\circ C$		50		150	μV
Offset Voltage Change	ΔV_{E1E2}	$\Delta I_B: 0.5 to 1.5 mA$		20		50	μV
Saturation Resistance	r_{E1E2}	$I_B = 1mA, I_{EE} = 10\mu A, f = 1Kc$	10	50	10	50	Ohms
			3N108/109		3N110/111		
Emitter-Base Leakage Current	I_{E1B} I_{E2B}	$V_{EB} = -25V$		0.1		0.5	nA
Emitter-Emitter Leakage Current	I_{E1E2}	$V_{EE} = +25V, V_{CB} = 0$ SHORTEO		0.1		0.5	nA
Emitter-Emitter Leakage Current	I_{E1E2}	$V_{EE} = \pm 25V Temp: 100^\circ C$		10		50	nA
Collector-Base Leakage Current	I_{CB}	$V_{CB} = -30V, I_{E1} = I_{E2} = 0$		0.25		0.5	nA
Emitter-Base Capacitance	C_{eb}	$V_{EB} = -6v, I_c = 0, f = 1Mc$		3		3	pf
Collector-Base Capacitance	C_{ob}	$V_{CB} = -6v, I_{E1} = I_{E2} = 0, f = 1Mc$		10		10	pf
Forward Current Gain	h_{fe}	$V_{CE} = 6.0V, I_c = 1mA, f = 4Mc$	3	-	3	-	

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